

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings of claims in the application:

Listing of Claims:

1. (currently amended) A thin-film magnetic head comprising:
magnetic layers each containing two or more elements of Co, Ni, and Fe;
wherein ~~said magnetic layers are plated films, and~~ a magnetic layer, of said
magnetic layers, ~~which is disposed near a magnetic gap is a plated magnetic film containing~~
contains Co, Ni, and Fe, with $20 \leq \text{Co} \leq 40 \text{ wt\%}$, $0 < \text{Ni} \leq 2 \text{ wt\%}$, and $60 \leq \text{Fe} \leq 80$
wt%, and ~~having~~ has a saturation magnetic flux density of 23,000 gauss or more, and the
thickness of said magnetic layer is 3 μm or more.
2. (canceled)
3. (currently amended) A process for production of a thin-film magnetic
head as defined in [[2]] claim 1, wherein the magnetic layers are formed in a plating bath
containing saccharin sodium as a stress relaxing agent.
4. (original) A process for production of a thin-film magnetic head as
defined in claim 3, wherein the plating bath contains saccharin sodium in an amount of 0.5-2
g/L.
5. (currently amended) A thin-film magnetic head of write-read separate
type in which a read element is a magneto-resistive effect element and a write element is an
inductive magnetic head,
wherein upper and lower magnetic cores of a write head partly or entirely have
magnetic layers consisting of magnetic films each containing two or more elements of Co,
Ni, and Fe, ~~the magnetic films are plated films, a magnetic layer, of the magnetic layers,~~
~~which is disposed near a magnetic gap is composed of a plated magnetic film, which is a soft~~
magnetic thin film containing CoNiFe, with $20 \leq \text{Co} \leq 40 \text{ wt\%}$, $0 < \text{Ni} \leq 2 \text{ wt\%}$, and 60
 $\leq \text{Fe} \leq 80 \text{ wt\%}$, and having a saturation magnetic flux density of 23,000 gauss or more, ~~and~~

~~the plated magnetic film is a soft magnetic thin film formed by electroplating in a plating bath having a pH value of 2 or less and the thickness of the magnetic layer is 3 μ m or more.~~

6. (new) A thin-film magnetic head as defined in claim 1, wherein said magnetic layer is the nearest layer to said magnetic gap of said magnetic layers.
7. (new) A thin-film magnetic head as defined in claim 5, wherein said magnetic layer is the nearest layer to said magnetic gap of said magnetic layers.
8. (new) A method for producing a thin-film magnetic head, comprising:
forming a magnetic core having magnetic layers; and
forming a magnetic gap film facing said magnetic core;
wherein a magnetic layer, of said magnetic layers, is formed by electroplating in a plating bath having pH value of 2 or less;
wherein said magnetic layer contains Co, Ni, and Fe, with $20 \leq \text{Co} \leq 40$ wt%, $0 < \text{Ni} \leq 2$ wt%, and $60 \leq \text{Fe} \leq 80$ wt%, and has a saturation magnetic flux density of 23,000 gauss or more.
9. (new) A method for producing a thin-film magnetic head as defined in claim 8, wherein said magnetic core includes an upper magnetic core and a lower magnetic core.
10. (new) A method for producing a thin-film magnetic head as defined in claim 9, wherein either of said upper magnetic core or said lower magnetic core has said magnetic layer.
11. (new) A method for producing a thin-film magnetic head as defined in claim 8, wherein said magnetic layer is the nearest layer to said magnetic gap of said magnetic layers.